IN THE CLAIMS

1 (Original). A method comprising:

forming a photoresist from a branched chain scission polymer.

2 (Original). The method of claim 1 including providing scissionable linkages and nonscissionable linkages in said polymer.

3 (Currently Amended). The method of claim 1 including providing a scissionable ~~scionable~~ linkage in a branch of said polymer.

4 (Original). The method of claim 1 including forming a photoresist including a polymer having a molecular weight greater than 10,000 Daltons.

5 (Original). The method of claim 1 including forming a photoresist including a polymer having a branch having a molecular weight greater than 5000 Daltons.

6 (Currently Amended). The method of claim 1 including forming a polymer including ~~oligo-4-hydroxstyrene~~ oligo-4-hydroxystyrene.

7 (Original). The method of claim 6 including forming tertiary carbonated linked branches.

8 (Original). The method of claim 6 including forming an oligo-1,4-dihydroxyphenylcarbonate-bis tertiary alcohol.

9 (Original). The method of claim 8 including appending a tertiary alcohol carbonate side chain on said polymer.